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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Huey-Shin YUAN et al.

Serial No. 09/811,667

Filed: March 20, 2001



Group Art Unit: 2163

Examiner:

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For: FAULT TOLERANT AND AUTOMATED COMPUTER SOFTWARE WORKFLOW

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Honorable Commissioner for Patents  
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

A handwritten signature in black ink, appearing to read "Scott M. Alter". The signature is fluid and cursive, with the first name "Scott" being more prominent.

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# INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)



ATTY. DOCKET NO.  
005957  
USA/Consilium/Consilium

SERIAL NO.  
09/811,667

APPLICANT  
Huey-Shin YUAN et al.

FILING DATE  
March 20, 2001

GROUP  
2163

## U.S. PATENT DOCUMENTS

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						Yes	No
	WO 95/34866	12/21/95	WO			X	
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	WO 99/25520	05/27/99	WO			X	
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	Hu, Albert, Kevin Nguyen, Steve Wong, Xiuhua Zhang, Emanuel Sachs, and Peter Renteln. 1993. "Concurrent Deployment of Run by Run Controller Using SCC Framework." IEEE/SEMI International Semiconductor Manufacturing Science Symposium. pp. 126-132.
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  (PTO-1449)			ATTY. DOCKET NO. 005957 USA/Consilium/Consilium		SERIAL NO. 09/811,667	
			APPLICANT Huey-Shin YUAN et al.			
			FILING DATE March 20, 2001		GROUP 2163	
<b>U.S. PATENT DOCUMENTS</b>						
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	WO 01/52055 A3	07/19/01	WO			X
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